

<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No. LSI1P239/03-1810	Application No.: Not yet assigned
	Applicant: Eib et al.	
	Filing Date Herewith	Group Not yet assigned

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
DCD	A1	Shroff et al., "Optical Analysis of Mirror Based Pattern Generation", Emerging Lithographic Technologies VII, pp. 550-559. © 2003.
Examiner /Daborah Chacko-Davis/		Date Considered 06/02/2006

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.